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**Zhang et al.**

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(54) **TARGET PROFILE FOR A PHYSICAL VAPOR DEPOSITION CHAMBER TARGET**

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(\*\*) Term: **15 Years**

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(21) Appl. No.: **29/610,166**

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**Related U.S. Application Data**

(62) Division of application No. 29/524,557, filed on Apr. 21, 2015, now Pat. No. Des. 797,067.

(51) **LOC (11) Cl.** ..... **13-03**

(52) **U.S. Cl.**

USPC ..... **D13/182**

(58) **Field of Classification Search**

USPC ..... D13/182; D15/144.1, 144.2, 199  
CPC ..... H01L 21/67742; H01L 21/0226; H01L 21/02263; H01L 21/02266; H01L 21/02269; H01L 21/02271; H01L 2224/75186; H01L 2224/76185; H01L 2224/76186; H01L 2221/68363

See application file for complete search history.

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(57) **CLAIM**

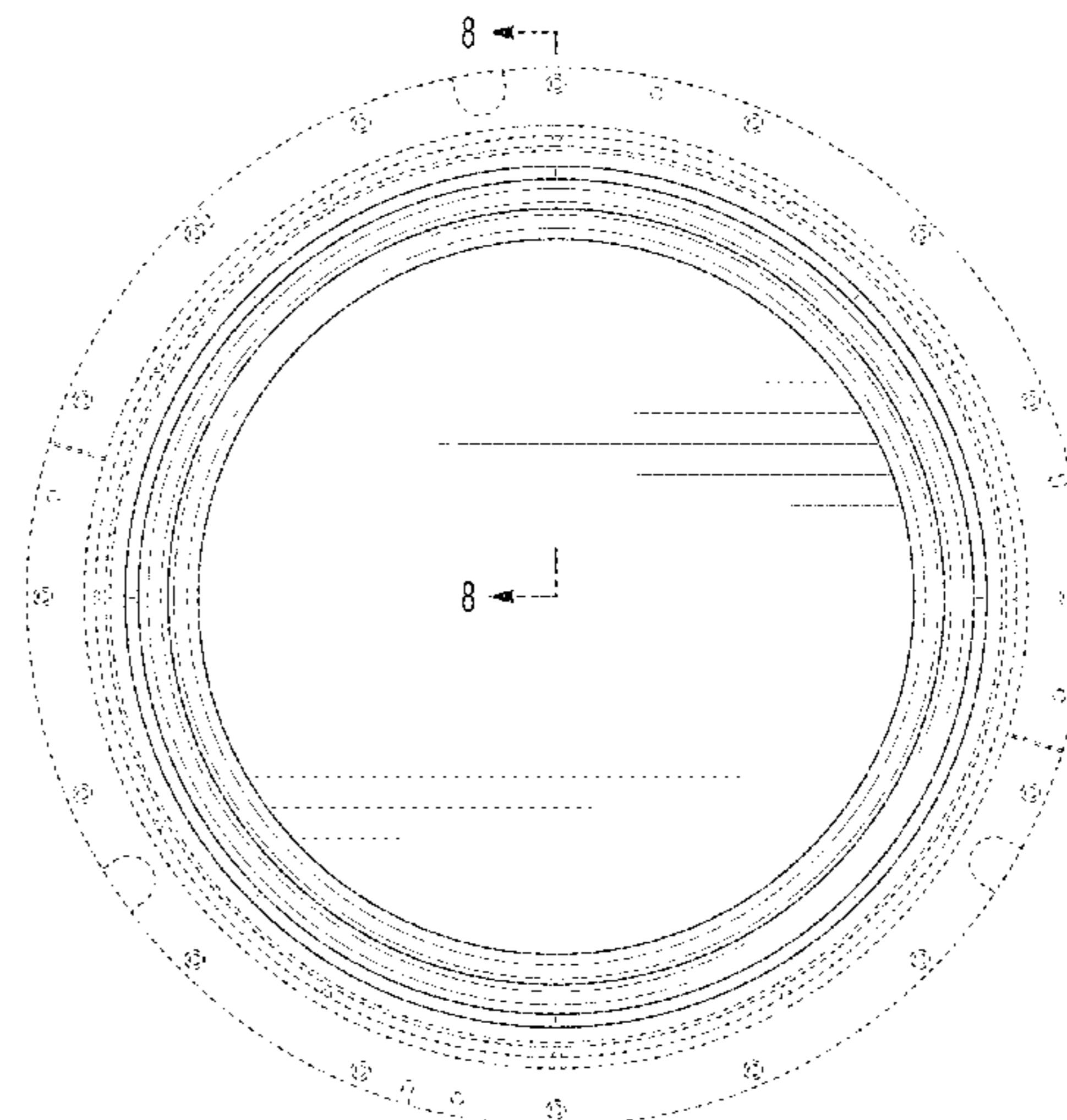
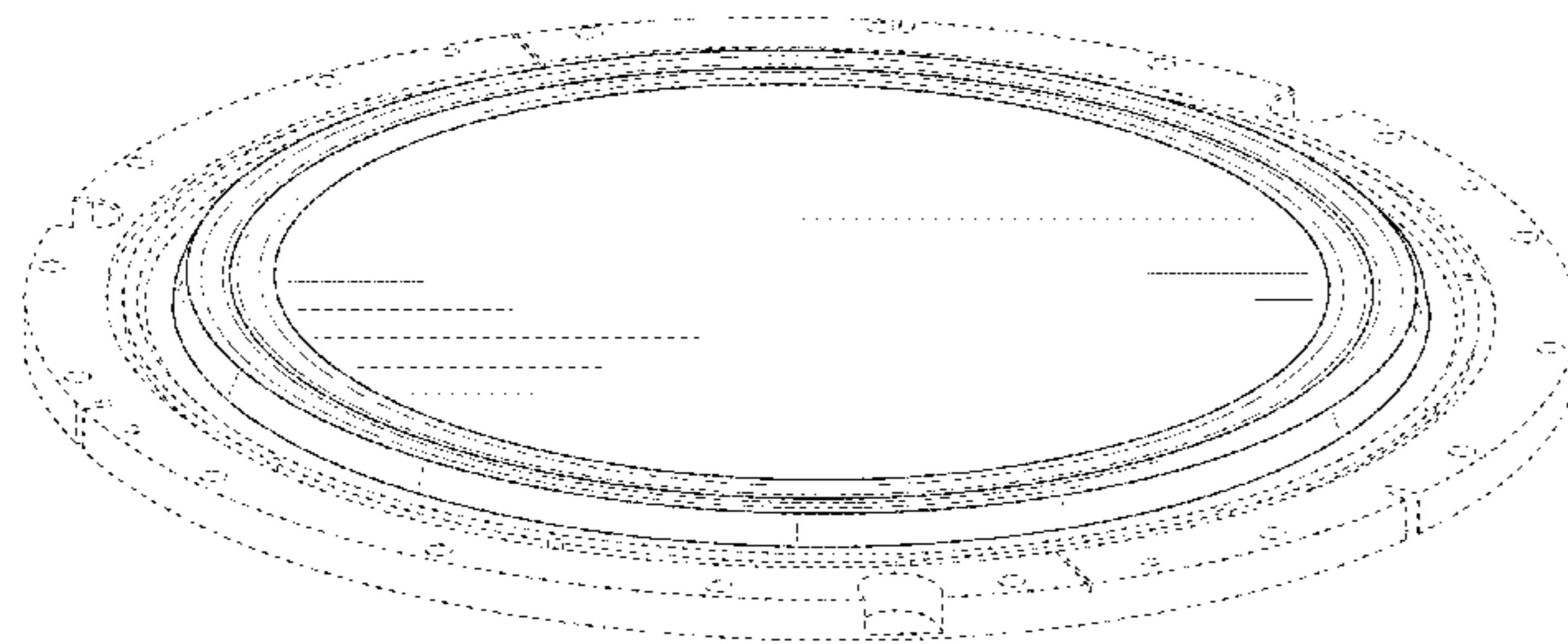
The ornamental design for a target profile for a physical vapor deposition chamber target, as shown and described.

**DESCRIPTION**

FIG. 1 is a perspective view of a target profile for a physical vapor deposition chamber target, showing my new design; FIG. 2 is a top plan view thereof; FIG. 3 is a bottom plan view thereof; FIG. 4 is a left side elevation view thereof; FIG. 5 is a right side elevation view thereof; FIG. 6 is a back elevation view thereof; FIG. 7 is a front elevation view thereof; and, FIG. 8 is a cross sectional view taken along line 8-8 of FIG. 2.

The dashed lines in FIGS. 1-8 represent disclaimed matter that forms no part of the claimed design.

**1 Claim, 6 Drawing Sheets**



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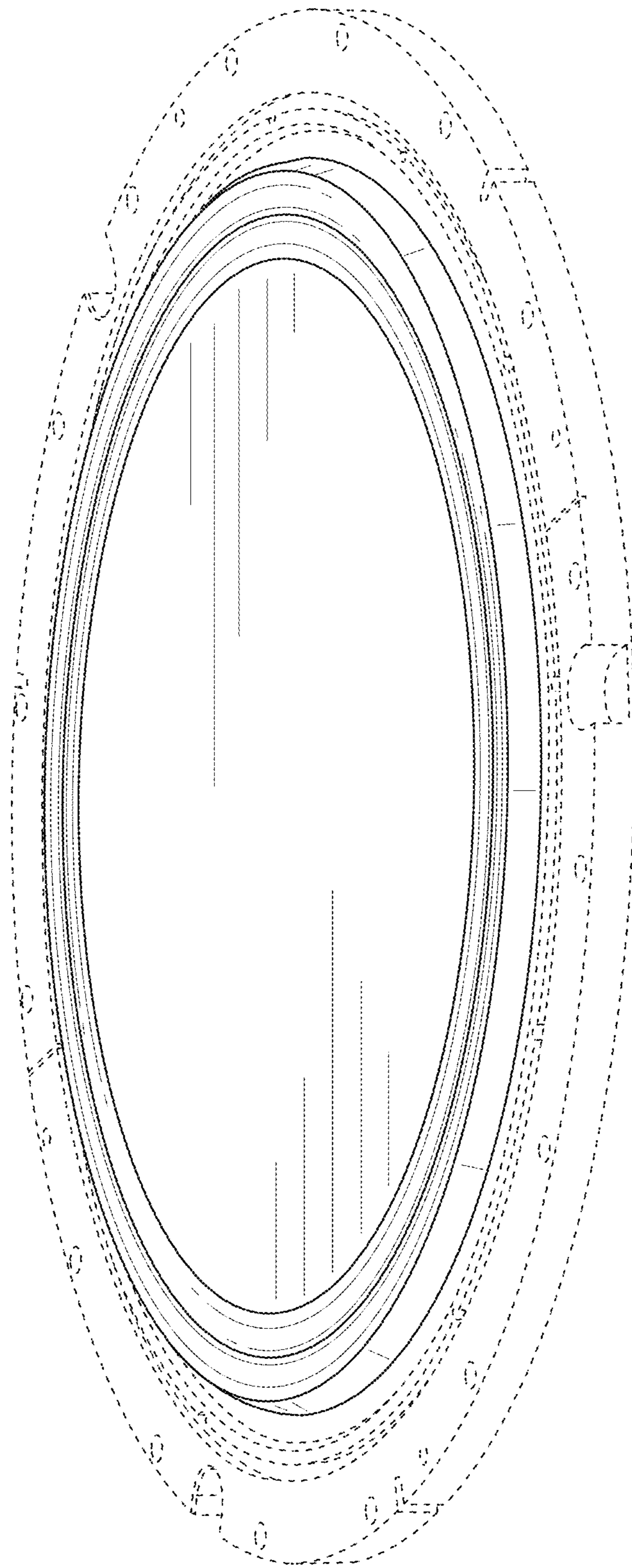


FIG. 1

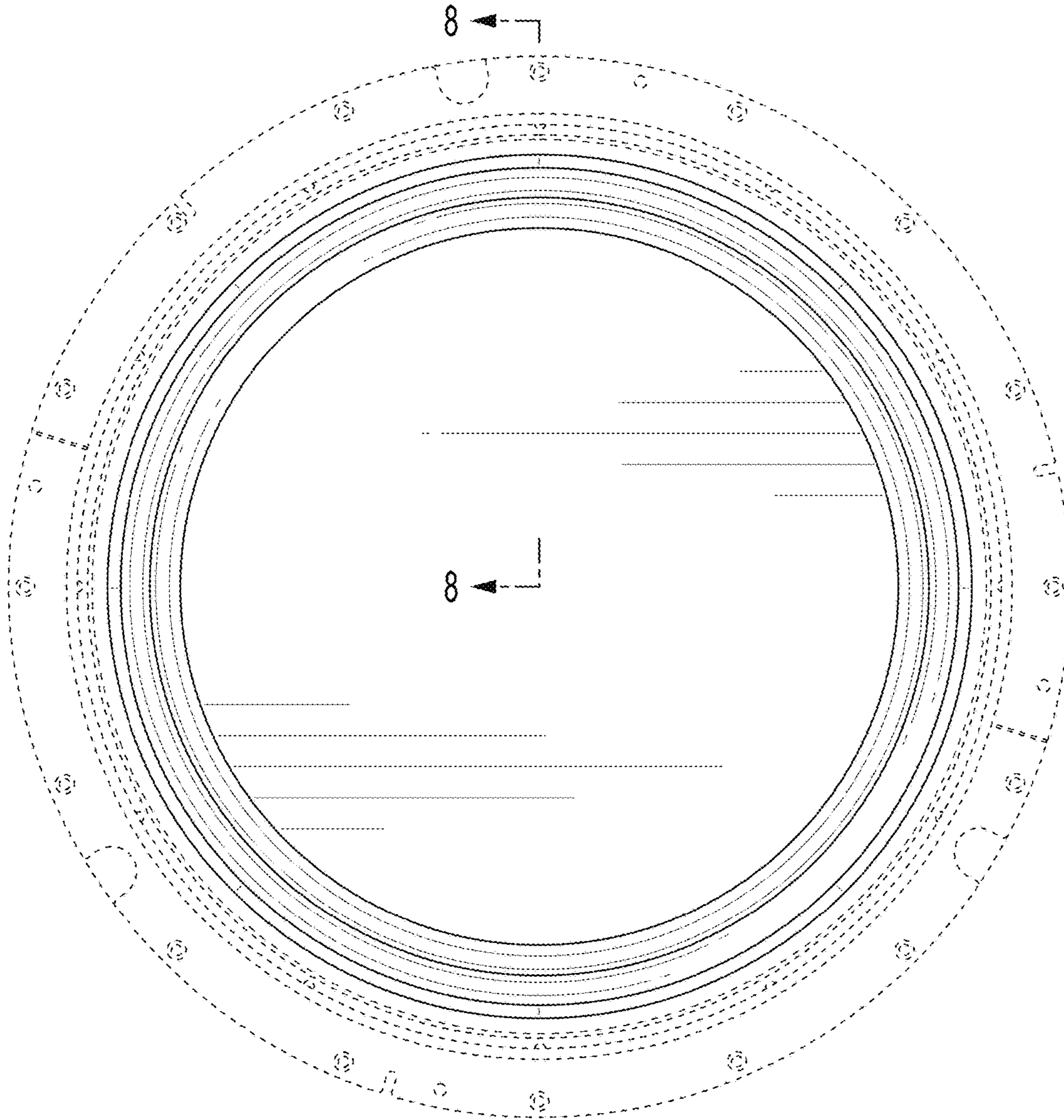


FIG. 2

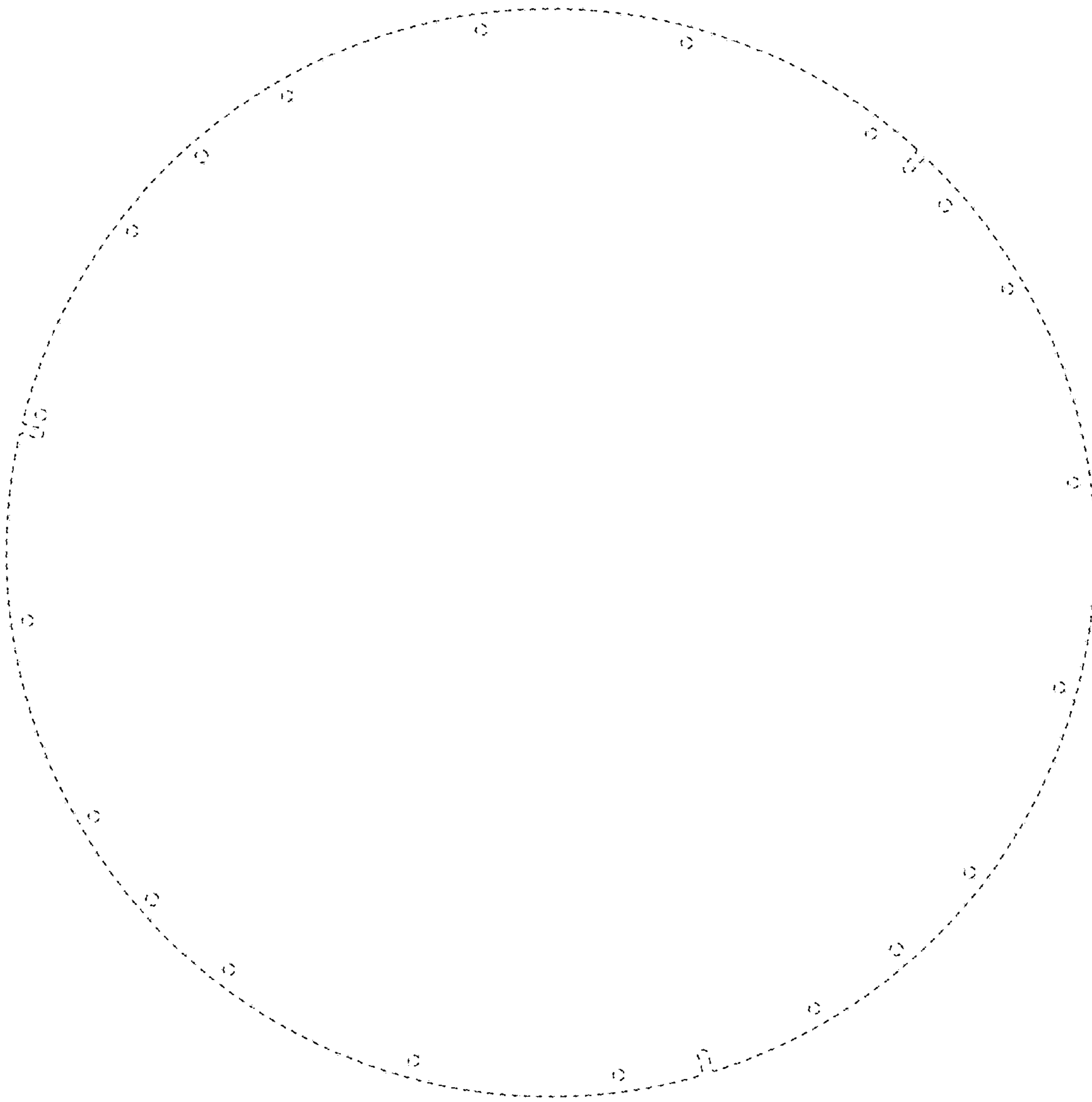


FIG. 3

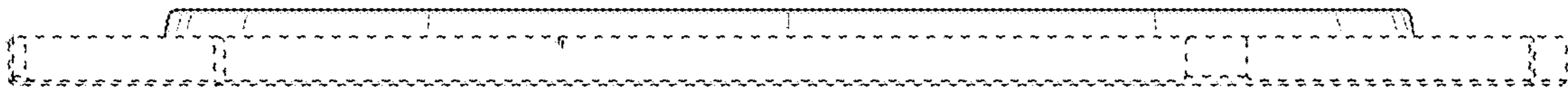


FIG. 4

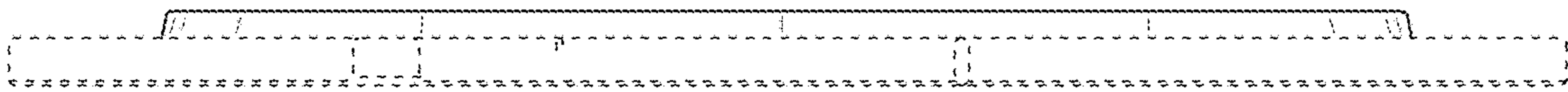


FIG. 5

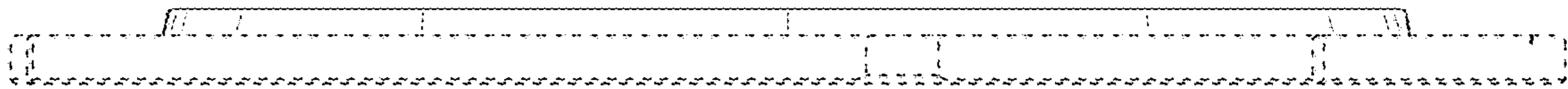


FIG. 6

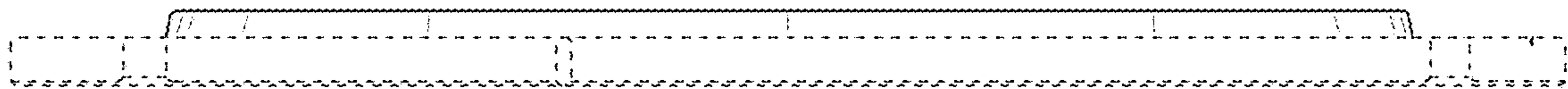


FIG. 7

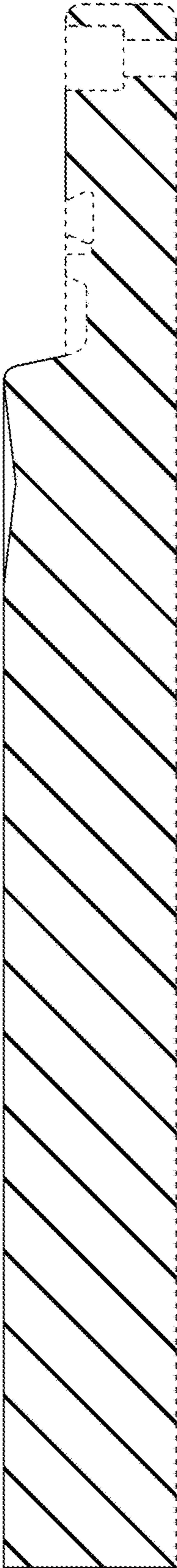


FIG. 8